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APPLICATIO	N NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
09/994,2	279	11/26/2001	Tony P. Chiang	PA1688US	8825	
22830	75	590 04/30/2002				
CARR & FERRELL LLP				EXAMINER		
2225 I SUITI		YSHORE ROAD		NHU, E	DAVID	
PALO	ALTO,	CA 94303		ART UNIT	PAPER NUMBER	
			•	2818		
			DATE MAIL ED: 04/30/2002			

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application No.		Applicant(s)	
•		09/994,279		CHIANG ET AL.	
	Office Action Summary	Examiner		Art Unit	
		David Nhu		2818	
eriod fo	The MAILING DATE of this communication ap or Reply	pears on the cover	sheet with the c	orrespondence address	
THE I - External after - If NC - Failur - Any II	ORTENED STATUTORY PERIOD FOR REPL MAILING DATE OF THIS COMMUNICATION. nsions of time may be available under the provisions of 37 CFR 1. SIX (6) MONTHS from the mailing date of this communication. period for reply specified above is less than thirty (30) days, a represended for reply is specified above, the maximum statutory period reto reply within the set or extended period for reply will, by statutely received by the Office later than three months after the mailing patent term adjustment. See 37 CFR 1.704(b).	.136(a). In no event, howev oly within the statutory minin I will apply and will expire SI te, cause the application to I	er, may a reply be tim num of thirty (30) day: X (6) MONTHS from become ABANDONE:	nely fited s will be considered timely. the mailing date of this communication. D (35 U.S.C. § 133).	
1)🖂	Responsive to communication(s) filed on 26	November 2001 .			
2a) 🗌	This action is FINAL. 2b)⊠ T	his action is non-fin	al.		
3)□ ispositi	Since this application is in condition for allow closed in accordance with the practice under on of Claims				
4)🛛	Claim(s) <u>1-22</u> is/are pending in the application	n.			
	4a) Of the above claim(s) is/are withdra	awn from considerat	tion.		
5)	Claim(s) is/are allowed.				
6)□	Claim(s) is/are rejected.				
7)	Claim(s) is/are objected to.				
•	Claim(s) 1-22 are subject to restriction and/or	election requireme	nt.		
pplicati	on Papers				
, —	The specification is objected to by the Examin				
10) 🗌	The drawing(s) filed on is/are: a)☐ acce	epted or b)⊡ objecte	d to by the Exa	miner.	
	Applicant may not request that any objection to the				
11)[	The proposed drawing correction filed on	_ is: a)□ approved	l b)∏ disappro	ved by the Examiner.	
	If approved, corrected drawings are required in re	eply to this Office action	on.	•	
12) 🔲 .	The oath or declaration is objected to by the E	xaminer.			
riority u	ınder 35 U.S.C. §§ 119 and 120				
13)	Acknowledgment is made of a claim for foreig	n priority under 35	U.S.C. § 119(a	)-(d) or (f).	
	☐ All b)☐ Some * c)☐ None of:				
•	1. Certified copies of the priority documen	its have been receiv	ved.		
	2. Certified copies of the priority documen	its have been receiv	ved in Applicati	on No	
* 0	3. Copies of the certified copies of the price application from the International Bee the attached detailed Office action for a lis	ureau (PCT Rule 17	7.2(a)).		
	acknowledgment is made of a claim for domes				
-	icknowledgment is made of a claim for domes $\cap$ .				
	Acknowledgment is made of a claim for domes				
ttachmen	(s)				
2) 🔲 Notic	e of References Cited (PTO-892) e of Draftsperson's Patent Drawing Review (PTO-948) nation Disclosure Statement(s) (PTO-1449) Paper No(s)	5) 🔲 1		(PTO-413) Paper No(s) Patent Application (PTO-152)	

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## **DETAIL ACTION**

## Election/Restrictions

1. Restriction to one of the following inventions is required under 35 U.S.C. 121:

Group I. Claims 1-21: draw to a sequential method for integrated, in-situ modification of a substrate and subsequent atomic layer deposition of a thin film onto the substrate classified in class 438, and subclass 905.

Group II. Claim 22: draw to an apparatus/a single-module system for atomic layer deposition of a film onto a substrate classified in lass 118, and subclass 715.

- 2. Inventions I and II are related as process and apparatus for its practice. The inventions are distinct if it can be shown that either: (1) the process as claimed can be practiced by another materially different apparatus or by hand, or (2) the apparatus as claimed can be used to practice another and materially different process. For example, Figure 1 shows an apparatus suitable for in-situ preclean/surface treatment, the reactive preclean step immediately preceding the copper seed layer deposition, as well as the copper seed layer deposition step, can be performed in a separate MII-ALD chamber integrated in an apparatus enabling vacuum transfer of the substrate such that steps 1 and 2 can be carried out in the first integrated cleaning/deposition chamber 400 and steps 3 and 4 can be carried out in the second integrated cleaning/deposition chamber 410 using the integrated apparatus as shown in figure 4A.
- 3. Because these inventions are distinct for the reasons given above and have acquired a separate status in the art as shown by their different classification, restriction for examination purposes as indicated is proper.

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Art Unit: 2818

4. Applicant is reminded that upon the cancellation of claims to a non-elected invention, the inventorship must be amended in compliance with 37 CFR 1.48(b) if one or more of the currently named inventors is no longer an inventor of at least one claim remaining in the application. Any amendment of inventorship must be accompanied by a petition under 37 CFR 1.48(b) and by the fee required under 37 CFR 1.17(i).

5. Any inquiry concerning this communication on earlier communications from the examiner should be directed to David Nhu, (703) 306-5796. The examiner can normally be reached on Monday-Friday from 7:30 AM to 5:00 PM.

The examiner's supervisor, David Nelms can be reached on (703) 308-4910.

The fax phone number for the organization where this application or proceeding is assigned is (703) 308-7724.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is (703) 308-0956

Dais Dly

David Nhu 🔊

April 26, 2002

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